

FIG. 1

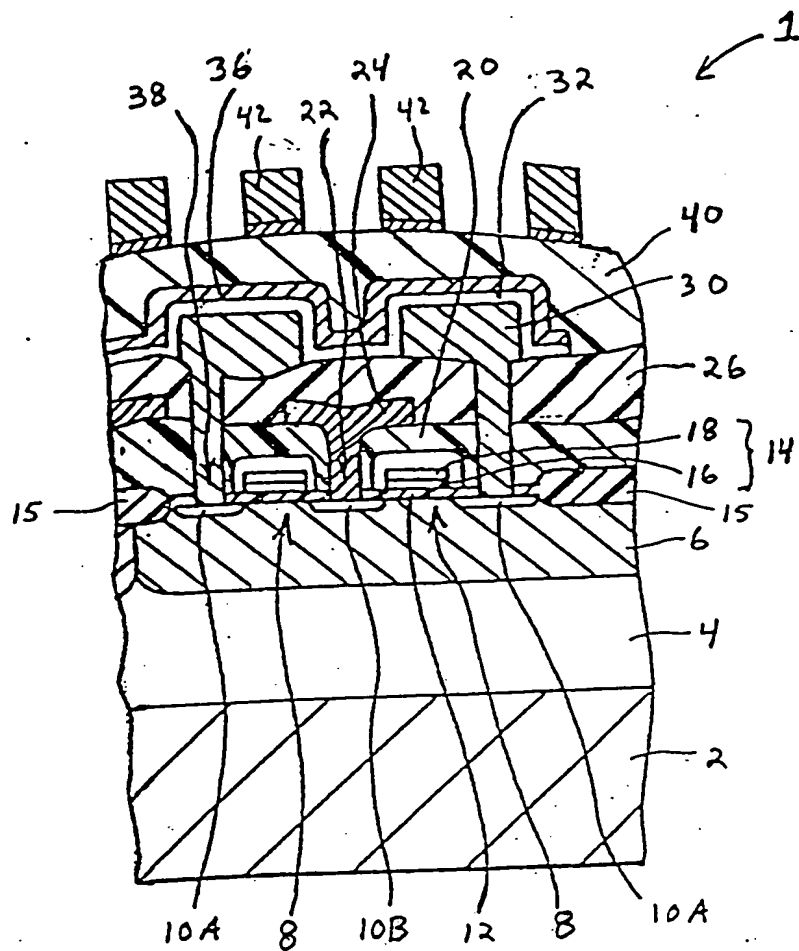


FIG. 1

FIG. 2

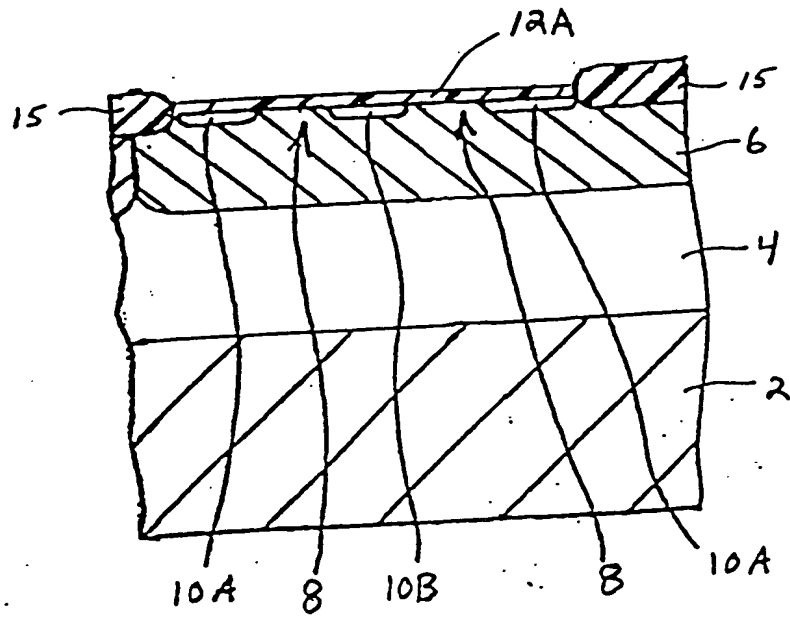


FIG. 2

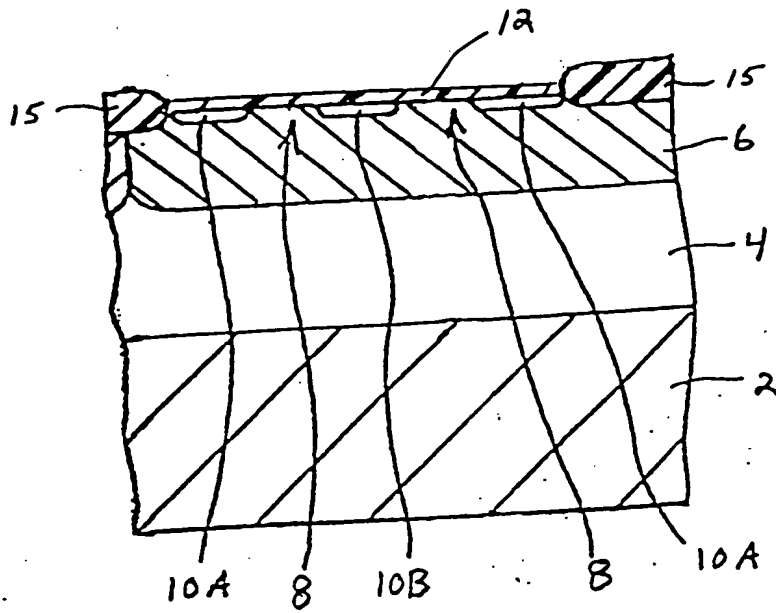


FIG. 3

109220:35921660

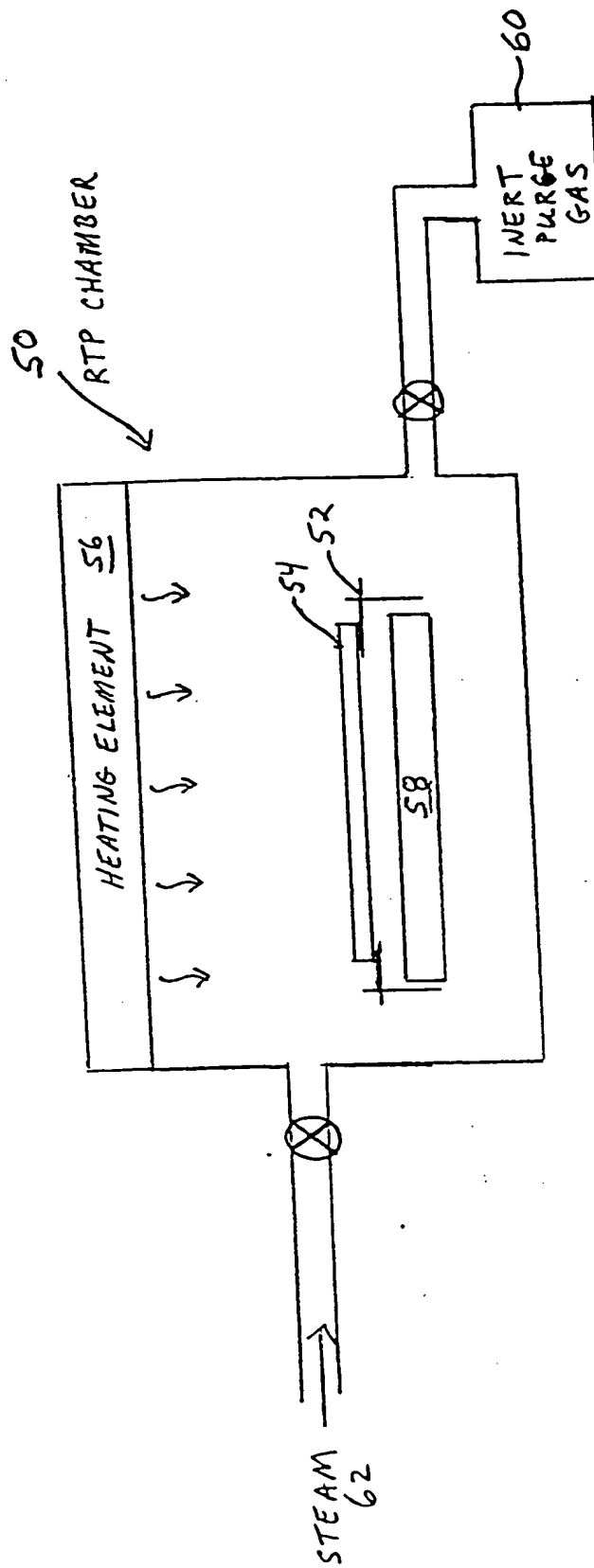


FIG. 4

A detailed cross-sectional view of a multi-layered assembly. The assembly consists of several layers and components, labeled with numbers. At the bottom, there is a base layer (2) with diagonal hatching. Above this is a layer (4) with horizontal hatching. The top section is a complex assembly of various components. A central component (12) is flanked by two side components (8). Above these are two more components (10A and 10B) with diagonal hatching. The topmost layer (30) has a complex profile with a central peak (32A) and side peaks (38). A bracket (14) groups the components 16, 18, and 26. Other labels include 20, 22, 24, 26, 15, and 6. The diagram uses different hatching patterns to distinguish between the various materials or layers.

FIG. 6

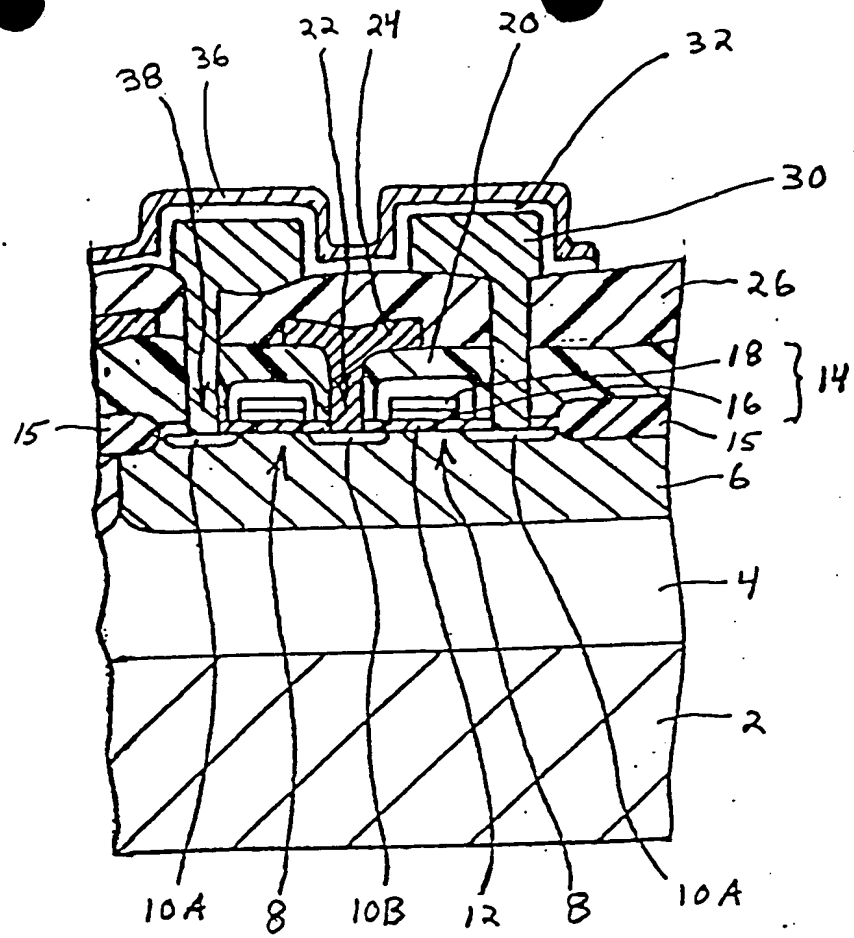


FIG. 7

DEPOSIT DIELECTRIC OR INSULATING FILM



SUBJECT THE INSULATING FILM TO A HEAT TREATMENT IN AN AMBIENT COMPRISING A STABILIZING GAS INCLUDING A GAS SELECTED FROM THE GROUP CONSISTING OF N_2 , O_2 , O_3 , NO, OR N_2O



SUBJECT THE INSULATING FILM TO A WET OXIDATION IN A RAPID THERMAL PROCESS (RTP) CHAMBER

FIG. 8

103220 15351 000